Contact Lithography: Proven, reliable methods for micro-scale patterning

Karl Suss MA-56
- 2,3,4” wafers and pieces
- 350W Lamp

Quintel Aligner
- 2,3” wafers and pieces
- IR backside alignment

Mask Making Suite: In-house mask making allows for more creativity and design flexibility at reduced cost

GCA 3600 Pattern Generator
- 6”x 6” Write Field
- 2μm minimum aperture
- ~5K flash/hr

GCA 3696 PhotoRepeater
- 6”x 6” Flash Field
- 1μm minimum
- 10x reduction
- 10 x 10mm maximum die

Contact: Rich Everly
Office: 813.974.5365
Fax: 813.974.3610
http://www.nrec.usf.edu